ULTRAPURE WATER® Asia 2011

Co-Located at Singapore International Water Week Suntec Exhibition Centre Singapore July 6-7, 2011

Conference Schedule (as of 6/8/2011)

Co-Moderators: Mr. Kiran Kekre, Singapore PUB

Mr. Alan Knapp, Siemens Industry Inc., Water Technologies

Wednesday, July 6

8:15-9:15 AM—Participant Registration

Rooms 301-302, Suntec Exhibition Centre

Water Business Forum Session Moderator: Mr. Kiran Kekre

9:00 AM—Networking

9:25 AM—Session Introduction

9:30 AM—Future Trends and Needs in High-Purity Water Treatment

Alan Knapp, Siemens Industry Inc., Water Technologies

9:50 AM—Asian Water Business Opportunities in UPW in Microelectronics/Photovoltaic

Mehbub Khan, Veolia Water Solutions & Technologies

10:20-10:45 AM—Tea Break

10:45 AM—PUB's Vision for Water Development in Singapore

Harry Seah, Director, Technology and Water Quality Office, Singapore PUB

11:15 AM—Asian Water Business Trends

Chris Sacksteder, Strategic Marketing Manager, Industrial Water/Power/UPW, Dow Water & Process Solutions

11:45 AM—Global Water Markets Overview

Mike Henley, ULTRAPURE WATER

12:00 PM-1:30 PM-Lunch Break

UPW Technology Forum

Moderator: Mr. Alan Knapp

1:30 PM—A New Concept of Water for Injection for a Global Healthcare Manufacturer

Dionisio Visintin, Veolia Water Solutions & Technologies Italia s.r.l.

2:00 PM—UV Oxidation with Persulfate for High-Purity Water in Microelectronics and Pharmaceutical Applications

Richard Woodling, J. Feng, J. Tan, A. Tan, Siemens Pte. Ltd.,

2:30 PM—Power Plant Steam: Water Cycle Makeup Treatment Raw Water Analysis

Mike Caravaggio, Integrated Solutions Pte. Ltd.

3:00-3:30 PM—Tea Break

3:30 PM—Preventing the Release of Nano Materials from Depleting Ion Exchange Beds by Using an Online Boron Analyzer

Rick Godec, GE Instruments

4:00 PM—Urea in Town Waters and High-Purity Water

Michael Abert, Ph.D.; Andreas Balz; Stefan A. Huber, Ph.D., DOC-Labor Dr. Huber

4:30 PM—New RO Elements Support Producing High-Purity Water with Less Energy

Yasushi Maeda and Jun Tonomura, Dow Chemical

Thursday, July 7

UPW Technology Forum

Moderator: Mr. Alan Knapp

8:30 AM—Participant Registration and Networking

8:45 AM—Water Conservation Strategy for Non-Domestic Sector

Ong Guo Rong, Singapore PUB

9:15 AM—Case Studies on Employing UF Technology to Reclaim Water from

Semiconductor Wastewater in Taiwan

Ronald Wen-Jung Chang, Peter Chin-Yu Wang, Dow Chemical

9:45 AM—Lowering the Operating Costs of Ion Exchange Equipment Using Degassing Membrane Contactors

Fred Wiesler, Membrana; Peter Shen, Shanghai Memtech Co. Ltd.; and J.S. Pan, Siemens-Ionpure Products

10:15 AM—Medium Pressure UV Efficiency Decomposes Water-Borne Chlorine Compounds

Uri Levy, Ph.D., Atlantium

10:45 AM—Tea Break

11:00 AM—Sodium and Silica Trace Measurement To Meet Today's Water Quality Specification in the Semiconductor Industry

Morris Teo, SWAN Analytical

11:30 AM—Comparison of Boron Rejection Capabilities of RO Membranes

Gareth Thomas, Back on Track

Noon-1:30 PM—Lunch Break

1:30 PM—Monitoring and Controlling UPW Organic Nitrogen Contamination to Improve Immersion Photolithography Process Control

Rick Godec, GE Instruments

2:00 PM—Modular Design Approach for UPW Supply Utilizing High-Efficiency RO

Bill McClain, Michael Holland, and Paul Tan, GE Power and Water, Water & Process Technologies

2:30 PM—Micro Media Column Filtration System for High Purity Water Production

Davis Arifin, Karthikeyan Sathrugnan, and Richard Woodling, Siemens Water Technologies

3:00 PM—Membrane Technology of UF and RO for High-Purity Water Used in Semiconductor and LCD Manufacturing

Toshi Hamada, Nitto Denko

^{*}Visit http://www.ultrapurewater.com for program updates.



Co-located at the Singapore International Water Week

This Conference covers world-class, state-of-the-art water treatment technologies for use by the Microelectronics, Biotechnology, Pharmaceutical, Power, and Manufacturing industries of the Asian continent.

Technical papers are presented by technical experts from throughout the industrialized nations. Water treatment technologies that are emphasized include Reverse Osmosis, Ultrafiltration, Nanofiltration, Electrodialysis, Ion Exchange, Electrodeionization, Microfiltration, and Instrumentation technologies. *All technical papers will be presented in English.*

Register early Limited space!

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